

Title (en)  
SHADOW MASK AND METHOD FOR PRODUCING A SHADOW MASK

Title (de)  
LOCHMASKE UND VERFAHREN ZUR HERSTELLUNG EINER LOCHMASKE

Title (fr)  
MASQUE A TROUS ET PROCEDE DE REALISATION D'UN MASQUE A TROUS

Publication  
**EP 1309896 A2 20030514 (DE)**

Application  
**EP 01967274 A 20010814**

Priority  
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• EP 0109405 W 20010814

Abstract (en)  
[origin: WO0214951A2] The invention relates to a shadow mask for particle rays, particularly ion rays comprising a silicon chip with a pattern therein, characterised in that the silicon chip has a metal coating on the side orientated towards the incident ion rays which stops said rays and dissipates heat. Also, disclosed is a method for producing the shadow mask.

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**G03F 1/16**

IPC 8 full level  
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